

ABSTRACT

A gas management assembly for a substrate processing apparatus includes: an exhaust module including a basic exhaust line that is formed to exhaust a chamber gas containing a process gas supplied to a chamber of the substrate processing apparatus to a discharge system; a recovery connection module including a recovery exhaust line that is branched from the basic exhaust line and formed to exhaust the chamber gas to a recovery system; and a control module configured to perform automatic switching of an exhaust path of the chamber gas from one of the basic exhaust line and the recovery exhaust line to the other based on at least one of an operation mode of the substrate processing apparatus, a pressure of the chamber, or a pressure of the recovery exhaust line.

Fig 1